		V
	Application No.	Applicant(s)
Notice of Allowshilling	10/643,136	KLESHOCK ET AL.
Notice of Allowability	Examiner	Art Unit
	Rakesh K. Dhingra	1763
The MAILING DATE of this communication appeall claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate commu IGHTS. This application is so	this application. If not included inication will be mailed in due course. THIS
1. X This communication is responsive to RCE dt. 9/21/06.		
2. X The allowed claim(s) is/are <u>1-13,37-39, 42-51 and 64.</u>		
3. Acknowledgment is made of a claim for foreign priority un	nder 35 U.S.C. § 119(a)-(d) o	or (f).
a) All b) Some* c) None of the:	-	
 Certified copies of the priority documents have 	e been received.	
2. Certified copies of the priority documents have	e been received in Application	n No
3. Copies of the certified copies of the priority do	cuments have been received	in this national stage application from the
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		a reply complying with the requirements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give		
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.	
(a) including changes required by the Notice of Draftspers	son's Patent Drawing Review	(PTO-948) attached
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date	,	
(b) including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or	in the Office action of
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t		
 DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT 	sit of BIOLOGICAL MATE FOR THE DEPOSIT OF BIO	ERIAL must be submitted. Note the DLOGICAL MATERIAL.
•		
Attachment(s) Ⅰ. ☑ Notice of References Cited (PTO-892)	5. ☐ Notice of Info	ormal Patent Application
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)		ımmary (PTO-413),
B. ☐ Information Disclosure Statements (PTO/SB/08),	Paper No./N	Mail Date Amendment/Comment
Paper No./Mail Date I. ☐ Examiner's Comment Regarding Requirement for Deposit	8 M Evaminaria 9	Statement of Reasons for Allowance
of Biological Material		. A
	9. 🔲 Other	·
		Rakesh K. Dhingra

U.S. Patent and Trademark Office PTOL-37 (Rev. 08-06)

DERTAILED AACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 9/21/06 has been entered.

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Joseph R. Jordan on 12/5/06.

The application has been amended as follows:

In the Claims

Claims have been amended as follows:

Claims 40, 41 & 63: (Cancelled)

64. (Presently Amended) An upper source shield configured to surround a material source and energy source in a removable top portion of a cooled and grounded chamber wall of a semiconductor processing apparatus for protecting said top portion from deposition, comprising:

an integral, annular metal element having at least four annular portions including a cylindrical top ring, a frusto-conical sloped ring, a cylindrical bottom ring, and a generally planar mounting element;

Application/Control Number: 10/643,136

Art Unit: 1763

the frusto-conical sloped ring having an upper smaller end contiguous with the top ring and a larger lower larger end contiguous with the bottom ring;

each of the rings having an inner surface and an outer surface;

the metal element having a continuous inner surface formed of the inner surfaces of said top, sloped and bottom rings, and an outer surface formed of the outer surfaces of said top, sloped and bottom rings;

the frusto-conical sloped-ring having an upper smaller end contiguous with the top ring and a larger lower larger end contiguous with the bottom ring; and

the mounting element is disposed on the outer surface of the sloped ring and having an inner edge- a bottom surface contiguous with a lower portion of the outer surface of the sloped ring at the back surface thereof and a mating surface contiguous with an upper portion of the outer surface of the sloped ring and configured to form intimate thermal contact and electrical contact with the removable top portion of the cooled and grounded chamber wall and to support the annular element thereon on the chamber wall.

1. (Presently Amended) A chamber shield assembly for a semiconductor-wafer vacuum processing apparatus comprising a plurality of shields including the upper source shield as-elaimed in of claim 64, wherein:

each of the plurality of shields is made of high thermal conductivity material to provide high thermal conductivity throughout each shield;

each shield has a mounting surface configured to provide intimate thermal contact with the wall of a chamber of the apparatus when secured thereto, the mounting surface having sufficient area to provide high thermal conductivity between the shield and the wall of the chamber.

Art Unit: 1763

42. (Presently Amended) The upper source shield as claimed in claim 63 64, wherein the mounting element comprises at least one slot extending from the mating surface to the bottom surface, wherein the slot is located on a circle having a diameter of approximately 584.7 mm and has an angular displacement of approximately 37.5 degrees.

44. (Presently Amended) The upper source shield as claimed in claim 63 64, wherein the mounting element comprises at least one hole extending from the mating surface to the bottom surface, wherein the hole is located on a circle having a diameter of at least approximately 586.7 mm and has a diameter of approximately 5 mm.

Allowable Subject Matter

Claim 1-13, 37-39, 42-51 and 64 allowed.

Reasons for allowance

The following is an examiner's statement of reasons for allowance:

Claim 64 – Prior art (US PGPUB 2004/0094402 – Gopajlraja et al) do not teach claim limitation "the mounting element is disposed on the outer surface of the sloped ring and having an inner edge a bottom surface contiguous with the a lower portion of the outer surface of the sloped ring at the back surface thereof and a mating surface contiguous with an upper portion of the outer surface of the sloped ring and configured to form intimate thermal contact and electrical contact with the removable top portion of the cooled and grounded chamber wall and to support the annular element thereon on the chamber wall." in the context of remaining limitations of the claim.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Application/Control Number: 10/643,136 Page 5

Art Unit: 1763

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rakesh K. Dhingra whose telephone number is (571)-272-5959. The examiner can normally be reached on 8:30 -6:00 (Monday - Friday).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571)-272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Rakesh Dhingra

PAM N. KACKAR, P.E. PRIMARY EXAMINER